

Abstract

Lithographic Apparatus, Optical Element and Device Manufacturing Method

5 An optical element, such as a multi-layer mirror for an EUV lithography apparatus, is provided, the optical element having a layer comprising one or more Buckminsterfullerenes. Typically the fullerenes are present as a capping layer, which is either provided as the outer capping layer of the optical element or forms a sub-capping layer which is adjacent to an outer capping layer formed of a different material. The fullerene containing layer(s) may
10 alternatively or additionally be present as an interlayer between two layers of a multi-layer mirror.